

METHOD OF EVALUATING PHOTOMASK BLANK-ASSOCIATED SUBSTRATE

ABSTRACT

The present invention is a method of evaluating a photomask blank-associated substrate, including the steps of: taking an image of a surface of the photomask blank-associated substrate to acquire a surface image, acquiring a contrast of the surface image from the acquired surface image, and evaluating the photomask blank-associated substrate on the basis of the acquired contrast of the surface image. This provides a method of evaluating a photomask blank-associated substrate that can conveniently evaluate the surface conditions (e.g., film qualities other than the transparency or the optical constants of an optical film and so on formed on a transparent substrate) of a photomask blank-associated substrate.

FIGURE: 1